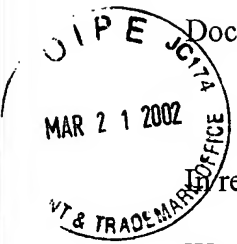


04.0.02



Docket No.: 50432-485

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re Application of

Wen-Jie QI, et al.

Serial No.: 10/023,328

Group Art Unit: 1765

Filed: December 20, 2001

Examiner: not yet assigned

For: NITRIDE OFFSET SPACER TO MINIMIZE SILICON RECESS BY USING POLY
REOXIDATION LAYER AS ETCH STOP LAYER

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, DC 20231

RECEIVED
MAR 26 2002
TC 1700

Dear Sir:

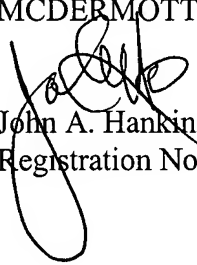
In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing

date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

Respectfully submitted,

MCDERMOTT, WILL & EMERY



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